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PATENT APPLICATION

RESPONSE UNDER 37 CFR §1.116
EXPEDITED PROCEDURE
TECHNOLOGY CENTER ART UNIT 2813

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Akira SHIMOKOHBE et al.

Application No.: 09/556,795

Filed: April 25, 2000

Group Art Unit: 2829
2813

Examiner: Asok K. Sarkar

Docket No.: 106096

For: A THIN FILM-STRUCTURE AND A METHOD FOR PRODUCING THE SAME

AMENDMENT AFTER FINAL REJECTION UNDER 37 CFR §1.116

Director of the U.S. Patent and Trademark Office
Washington, D.C. 20231

Sir:

In reply to the Office Action mailed November 30, 2001, please amend the above-identified application as follows:

IN THE CLAIMS:

Please replace claim 3 as follows:

3. (Twice Amended) A method for producing a thin film-structure comprising the steps of:
forming on a substrate a thin film made of an amorphous material having a supercooled liquid phase region,
heating the thin film to a temperature within the supercooled liquid phase region so that the thin film has a viscous flow between 10^8 - 10^{13} Pa·S and thereby deforming the thin film to a given shape without the use of an external force, and

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